

FORM PTO-1449 (Modified)		Attorney Docket No.: A524R1/T289	Application No.: 09/187,551
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		Applicant: MUSAKA et al.	
		Filing Date: November 5, 1998	Group: 1762

Reference Designation		U.S. PATENT DOCUMENTS			Page 1	
Examiner Initial	Document No.	Date	Name	Class	Sub-class	Filing Date (If Appropriate)
AA	5,483,636	01/09/96	Saxena	395	183.01	03/29/95
AB	5,750,211	05/12/98	Weise et al.	427	579	07/16/93

FOREIGN PATENT DOCUMENTS

	Document No.	Date	Country	Class	Sub-class	Translation (Yes/No)
AC	0 666 340 A1	08/09/95	EP	C23C 16/44	C23C 16/52	in English Yes
AD	0 724 286 A1	07/31/96	EP	H01L 21/316	C23C 16/40	in English Yes
AE	07-29975	01/31/95	JP	H01L 21/768	H01L 21/205	Yes(abstract)

OTHER ART (Including Article Title, Date, Pertinent Pages, Etc.)

AF	Bazyleko, M. V. et al., "Pure And Fluorine-Doped Silica Films Deposited In A Hollow Cathode Reactor For Integrated Optic Applications", <i>J. Vac. Sci. Technol. A</i> 14(2), Mar/Apr 1996, pp. 336-345.
	Mizuno et al., "Dielectric Constant and Stability of Fluorine Doped PECVD Silicon Oxide Thin Films", <i>Thin Solid Films</i> 283 (1996) pp. 30-36. Sept.

EXAMINER

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3/15/00

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MAY 20 1999

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and note considered. Include copy of this form with next communication to applicant.

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